

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L1	187	(tungsten adj film) with (tungsten adj silicide adj film)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:54
L2	12	(tungsten adj film) with (tungsten adj silicide adj film) same plug	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:54
L3	29	(tungsten adj film) with (tungsten adj silicide adj film) same (trench or via or opening or plug)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:55
L4	1	((tungsten adj film) with (tungsten adj silicide adj film) same (trench or via or opening or plug)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:55
L5	1	((tungsten adj (layer or film)) with (tungsten adj silicide adj film) same (trench or via or opening or plug)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:55
L6	3	((tungsten adj (layer or film)) with (tungsten adj silicide adj (layer or film)) same (trench or via or opening or plug)).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:57
L7	45	((tungsten adj (layer or film)) with (tungsten adj silicide adj (layer or film))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:57
L8	3	((tungsten adj (layer or film)) near10 (on or over or top or above) near10 (tungsten adj silicide adj (layer or film))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:58
L9	42	((tungsten adj (layer or film)) near10 (tungsten adj silicide adj (layer or film))).clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:59

L10	1	((tungsten adj (layer or film)) near10 (tungsten adj silicide adj (layer or film))).clm. and coil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 18:59
L11	8	((tungsten adj (layer or film)) near10 (tungsten adj silicide adj (layer or film))) and coil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:00
L12	9	((tungsten adj (layer or film)) with (tungsten adj silicide adj (layer or film))) and coil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:00
L13	2	((tungsten adj (layer or film)) with (tungsten adj silicide adj (layer or film))) and (tungsten adj coil)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:00
L14	5	(tungsten adj silicide) and (tungsten adj coil)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:01
L15	24	(tungsten with coil with (sputter or sputtering or sputtered))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:01
L16	18	(tungsten near10 coil with (sputter or sputtering or sputtered))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:02
L17	15	(tungsten near10 coil near10 (sputter or sputtering or sputtered))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:03
L18	12684	(tungsten adj silicide)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:03
L19	4818	(tungsten adj silicide) and (sputter or sputtering or sputtered)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:03

L20	293	(tungsten adj silicide) and (sputter or sputtering or sputtered) and coil	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:03
L21	278	(tungsten adj silicide) and (sputter or sputtering or sputtered) and coil and (deposit or depositing or deposited or deposition)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:04
L22	255	(tungsten adj silicide) and (sputter or sputtering or sputtered) and coil and (deposit or depositing or deposited or deposition) and plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:04
L23	59	(tungsten adj silicide) same(sputter or sputtering or sputtered) and coil and (deposit or depositing or deposited or deposition) and plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:04
L24	59	(tungsten adj silicide) same (sputter or sputtering or sputtered) and coil and (deposit or depositing or deposited or deposition) and plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:04
L25	2	(tungsten adj silicide) same (sputter or sputtering or sputtered) same coil and (deposit or depositing or deposited or deposition) and plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:04
L26	2	(tungsten adj silicide) same (sputter or sputtering or sputtered) same coil same (deposit or depositing or deposited or deposition) and plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:04
L27	2	(tungsten adj silicide) same (sputter or sputtering or sputtered) same coil same (deposit or depositing or deposited or deposition) same plasma	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:05
L28	1347	(barrier same (tungsten or W) same ((tungsten adj silicide) or WSi))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:06
L29	1323	(barrier same (tungsten or W) same ((tungsten adj silicide) or "WSi.sub.x"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:07

L30	763	(barrier near10 (tungsten or W) same ((tungsten adj silicide) or "WSi.sub.x"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:07
L31	380	(barrier near10 (tungsten or W) near10 ((tungsten adj silicide) or "WSi.sub.x"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:07
L32	143	(barrier near10 (tungsten or W) near10 ((tungsten adj silicide) or "WSi.sub.x")).ti,ab,clm.	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:08
L33	17	(barrier near10 (tungsten or W) near10 ((tungsten adj silicide) or "WSi.sub.x") near10 (plug or via or opening or trench))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/04/08 19:14